

Current and Emerging Memory Technology Landscape

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A New Era Emerging for Memory?

Convergence of many factors/pressures:

- Increasing importance of memory to user experience
 - Our lives are becoming one big shared database, with IOPs becoming more important than MIPs
- Both NAND and DRAM facing scaling challenges
 No hard "wall," but increasing complexity
- Explosion of "new" memory storage concepts
 - > New storage physics are enabling new usage models
- Evolving memory hierarchy
 - New features, relentless cost reduction, and need for I/O performance are remaking the memory hierarchy

Memory is moving from a support role to a defining system role



Memory-Relevant Trends





Just as memory usage becomes "interesting"...

- "Planar" nonvolatile (NVM) technology scaling is becoming difficult:
 - MOS transistor-based cell; charge-storage memory effect
 - Starting to encounter physical scaling limitations
 - Manifesting first as reliability \rightarrow endurance/retention
 - Increasing degree of memory management required for functionality
 → memory abstraction
- No scaling "brick wall," but complexity is increasing the level of management required to maintain added functionality



Flash Cell Scaling Challenges

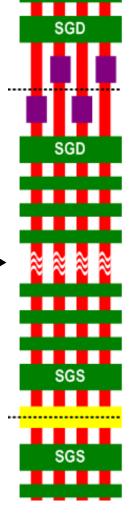
Basic NAND structure has changed little over time...

0.5 µm

Main scaling issues:

- Few-electron problem
- Capacitance limitations
- Tunnel and interpoly charge retention
- Voltage isolation
- Parasitic charge trapping
- Read and write noise

State of the art: 25nm NAND



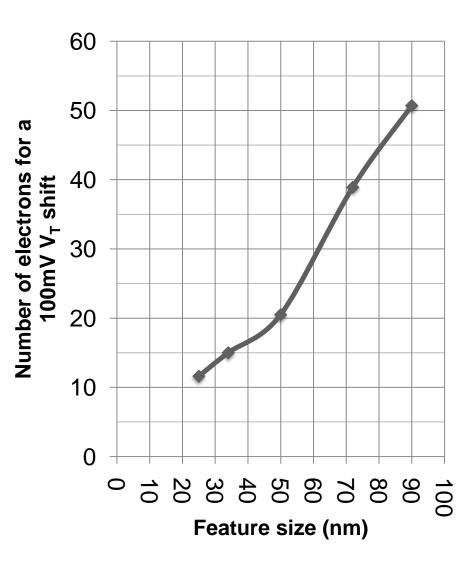




Few-Electron Effect

For a floating-gate cell, the number of electrons required for a V_T shift scales with the FG capacitance

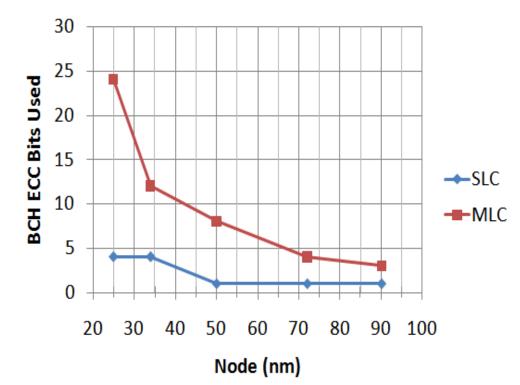
At 25nm, MLC states are separated by 30–50 electrons (300–500mV)





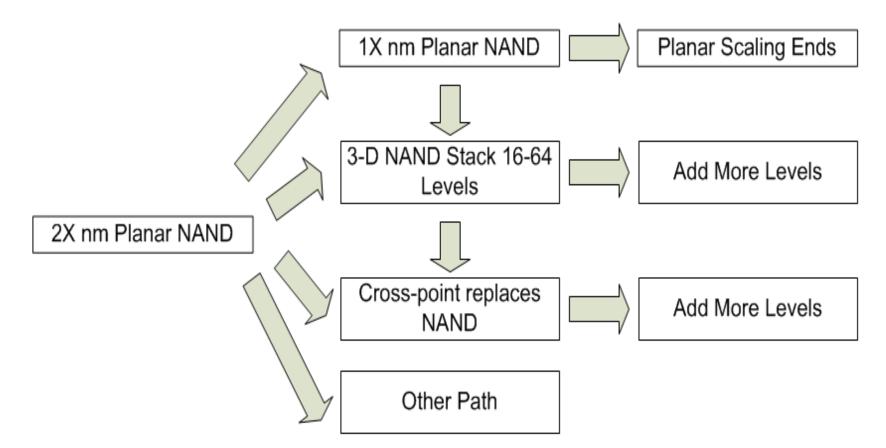
NAND media scaling issues are being addressed through system-level management tools such as error correction, wear leveling, and block retirement—

but straightforward options are being exhausted





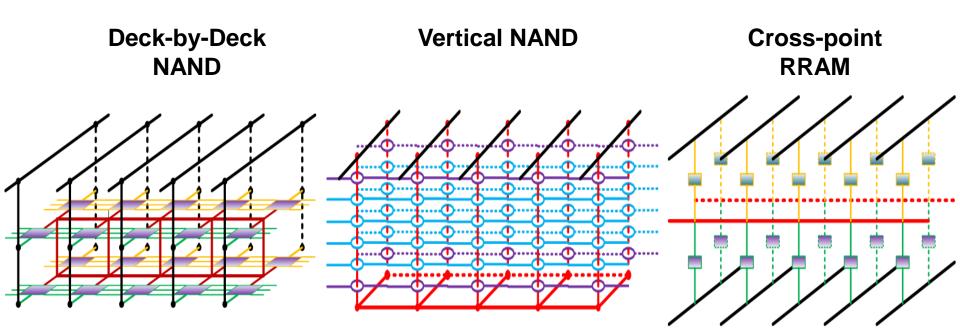
Several possible scenarios...





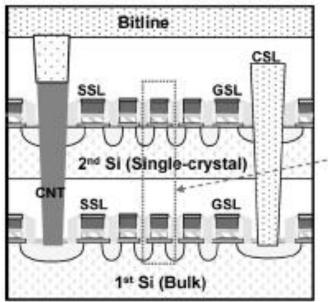
Going 3-D → Three Major Options

- Deck-by-deck NAND SOI for upper decks
- Vertical NAND Vertical cells arranged in vertical strings
- Cross-point RRAM (resistive RAM) cells





3-D NAND Highlights



Deck-by-Deck: Dual-Deck

(a) P-BiCS (b) TCAT Source Line Bit Line Poly-Si Channel SSL SG Gate W-Gate Tunnel ox. Control Gate (W/L) Trap SiN Blocking Layer GSL Gat Fig. 1 Schematic of P-BiCS flash memory. CSL p-Sub Vertical NAND

- Significant industry effort on 3-D NAND development
- Conference publications showing promising results
- Possibility to extend NAND roadmap for several generations



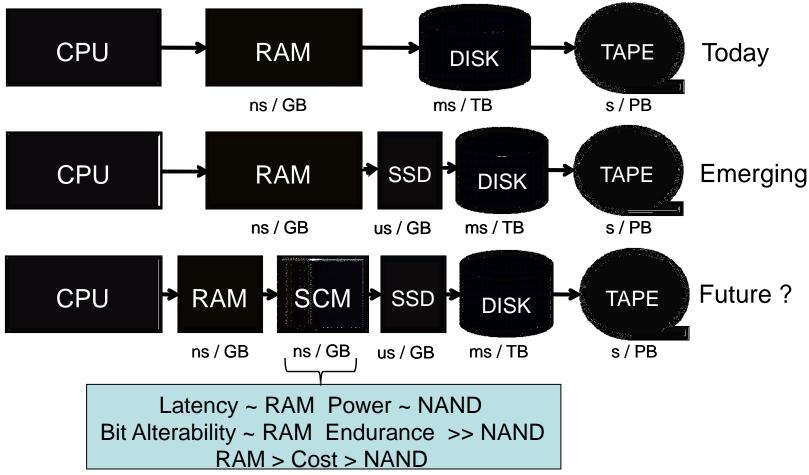
Requirements for NAND Successor

- Cost structure beat NAND costs:
 - MLC-capable
 - 3-D-stackable
 - Simple process flow
- Scalability:
 - In x & y with lithography
 - In z with number of layers
- Reliability, performance, and power:
 - To meet emerging usage requirements
 - At component and system level



NAND Successor Not the Only Target

New Memory Hierarchy? Balancing Latency, Power, Cost, and Endurance





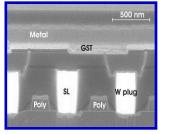
Alternative New-Memory Concepts

FERAM

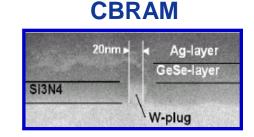


MRAM

PCM



MOx-RRAM



Polymer RRAM

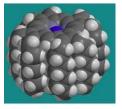
FLECTRODE







Molecular



Explosion of "new" memory concepts:

- New storage materials, new storage concepts
- Many ideas, varying functionality/cost, most unproven



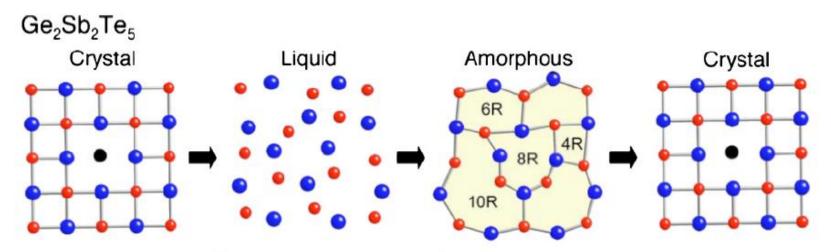
Phase Change Memory Case Study

- Of the emerging RRAMs, PCM is the most mature:
 - Already in low-volume production
 - Demonstrated at Gb density vs. other EM at Mb density
 - Announced by multiple memory companies
- PCM has been heavily studied for 10+ years:
 > Widely published lots of good-quality technical content
 > Chalcogenide-based material understanding is fairly mature
 > Many active researchers in both industry and academia
- Provides insight into other emerging-materials systems:
 Many of the RRAMs share similar attributes with PCM



Why Phase Change Materials Are Interesting

- Amorphous and crystalline phase structures are similar
 → Easy transition between phase states
- Material contains voids and vacancies
 → Easy movement of atoms
- Volume of crystalline and amorphous phase closely matched
- Large set of materials to choose from for best performance



Flash Memory Summit 2011 Santa Clara, CA

Terao, Japanese Journal of Applied Physics 48 (2009) 080001



Phase Change Memory Concept

Storing mechanism:

Amorphous/polycrystal phases of a chalcogenide alloy; example shown is $Ge_2Sb_2Te_5$ (GST)

Sensing mechanism:

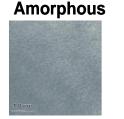
Resistance change of the GST

Writing mechanism:

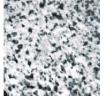
Self-heating due to current flow (Joule effect)

Cell structure:

1 diode, 1 resistor (1D/1R)

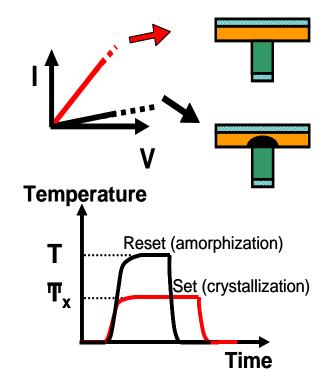


Crystalline



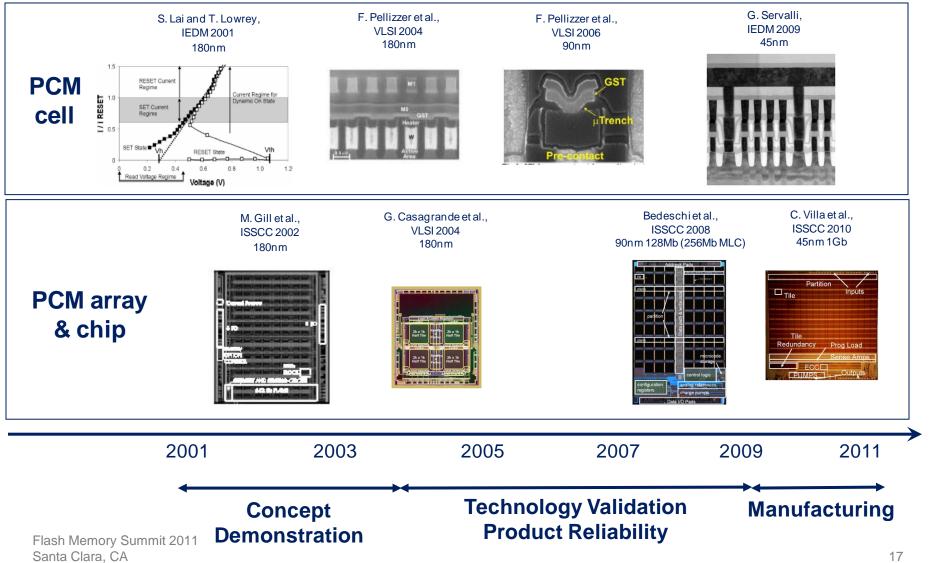


/ Low resistivity





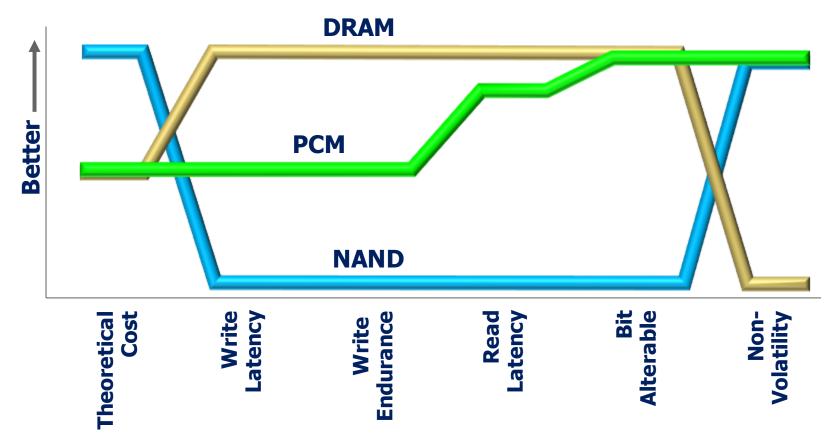
History of PCM Development





PCM Characteristics

PCM offers attributes of RAM and NAND Roughly aligned to "storage-class memory"





PCM Applications Opportunities

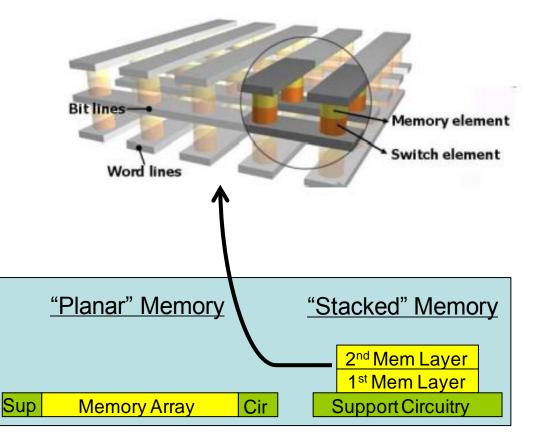
- Wireless system to store XiP, semi-static data
 - PCM bit alterability allows direct-write memory
- Solid state storage subsystem to store frequently accessed pages and elements that are easily managed when manipulated in-place
 - PCM caching to improve performance & reliability
- Computing platforms taking advantage of nonvolatility to reduce power
 - PCM offers endurance and write latency that are compelling for a number of novel solutions



3-D Cross-Point Memory– Best Chance to Reach NAND Cost?

Cross-point memory *features*:

- Simple small 4F² cell
 → low potential cost
- Suitable for 3-D stacking
 → cell size (4/n)F²
- Array over circuitry
 → better array efficiency

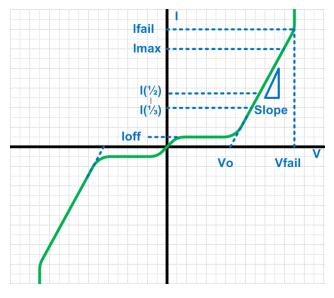




3-D Cross-Point Memory– Best Chance to Reach NAND Cost?

Cross-point memory *challenges*:

- Compatible diode selector
- Must be multilevel cell capable (2–3 bits/cell)
- Must be able to stack layers of cells
- Low temperature processing
- Interconnect-intensive



Selector "diode" requirements:

 $V_{prog}/2$

V_{prog}

 $V_{proq}/2$

V_{prog}/2

V_{prog}/2

0 V

- A "non-ohmic" device
- Compatible with memory element
- Stringent on/off current requirements
- Unipolar- or bipolar-depending cell



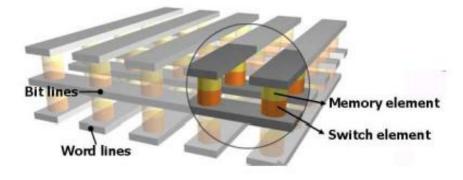
Wide Range of Cross-Point Options and Combinations

Selection Device

- Homojunctions \rightarrow polySi p/n junctions
- Heterojunctions → P-CuO/n-InZnO
- Schottky diode → Ag/n-ZnO
- Chalcogenide ovonic threshold switching (OTS) materials
- Mixed ionic electronic conduction (MIEC) materials

Memory Device

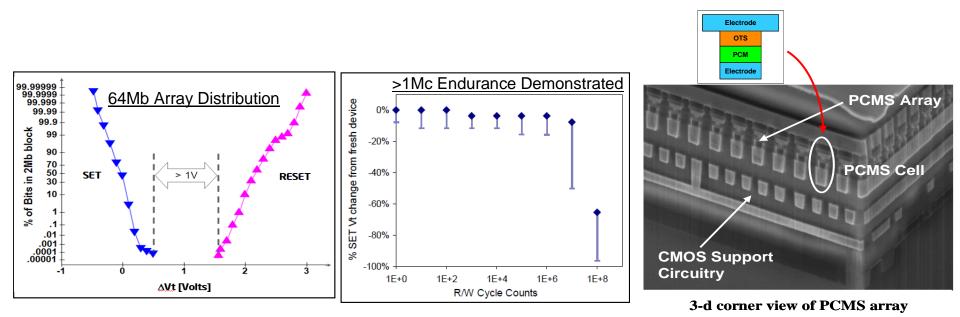
- STTRAM
- RRAM or CBRAM
- PCM





Stacked phase change memory 64Mb demonstrator:

- Same PCM memory concept
- Ovonic threshold switch OTS as selection device
- OTS is the same class of materials as PCM but "frozen" in the amorphous phase





Summary: A New Era Emerging for Memory!

- Increasing importance of memory to user experience:
 - Our lives are becoming one big shared database
- Increasing importance of memory to system performance:
 Server performance and power, client portability, and instant-on
- Both NAND and DRAM facing scaling challenges:
 - > No hard "wall," but increasing complexity
 - New storage concepts are emerging for cost and features
- Evolving memory hierarchy around NVM capabilities:
 - ➢ Moore's Law cost treadmill → NVM becoming high-performance storage
 - \succ New memory features \rightarrow possibility of storage-class memory

Memory is moving from a support role to a defining system role

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